

Process type factors	Process gas <i>i</i>								
	CF ₄	C ₂ F ₆	CHF ₃	CH ₂ F ₂	C ₃ F ₈	c-C ₄ F ₈	NF ₃ remote	NF ₃	SF ₆
Etch 1-U _i	0.7	0.4	0.4	N/A	N/A	0.2	N/A	N/A	0.4
Etch P _{CF₄}	N/A	0.2	N/A	N/A	N/A	0.1	N/A	N/A	N/A
Etch P _{C₂F₆}	N/A	N/A	N/A	N/A	N/A	0.1	N/A	N/A	N/A
CVD 1-U _i	N/A	0.6	N/A	N/A	0.1	0.1	N/A	0.3	0.4
CVD P _{CF₄}	N/A	0.2	N/A	N/A	0.2	0.1	N/A	N/A	N/A

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